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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Akshey Seghal

Application No.: 10/620,895

Filed: July 16, 2003

For: COMPOSITIONS AND METHOD FOR
REMOVING PHOTORESIST AND/OR
RESIST RESIDUE AT PRESSURES
RANGING FROM AMBIENT TO
SUPERCRITICAL

Confirmation No.: 8934

Group Art Unit: 1746

Examiner: B.S. Carrillo

**CHANGE OF ATTORNEY OR AGENT'S
ADDRESS IN APPLICATION
(37 CFR 1.8(a))**

353 Sacramento Street, Suite 2200
San Francisco, CA 94111
(415) 772-4900

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

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Box 1450 Alexandria, VA 22313-1450 on Sept. 27, 2004.
STALLMAN & POLLOCK LLP

Dated: 09/27/2004

By: Georgia K. Smith

Georgia K. Smith

Sir:

Please send all correspondence for this application to:

STALLMAN & POLLOCK LLP
Attn: Kathleen A. Frost
353 Sacramento Street, Suite 2200
San Francisco, CA 94111
Customer No.: 28584

Please direct all telephone calls to:

Kathleen A. Frost
Telephone: (415) 772-4900
Facsimile: (415) 398-2890

Respectfully submitted,

STALLMAN & POLLOCK LLP

Dated: September 27, 2004

By: Jason D. Lohr

Jason D. Lohr (Reg. No. 48,163)

Attorneys for Applicant(s)

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